

Advances in Direct Write Lithography

Grenoble, 10th Sep 2019

Direct write lithography is increasingly used for prototyping and manufacturing.

We invite all interested engineers and scientists to join this workshop about state-of-art technologies and applications of direct write lithography.

Venue

Mercure Grenoble Meylan Hotel
34 Avenue de Verdun, 38240 MEYLAN
(Public transport: Bus C1 direction Meylan from Grenoble station (every 10 min) to «Carronnerie - Ile d'Amour». Hotel directly there.)

Registration

Please register until 5th Sep using this link:

<https://forms.gle/yoCu9RqAUoncgl369>

or send an email to Dominique Cauquot:
cauquot@innodys.com

Registration required, participation is free

Program

- 10:00 Welcome Reception
Coffee & snacks
- 11:00 *Pushing the limits of direct write laser lithography*
Sven Preuss, Heidelberg Instruments
- 11:30 *E-beam Direct Write Lithography: Technology capabilities for a large field of applications*
Isabelle Servin, CEA LETI
- 12:00 *NanoFrazor lithography for advanced 2D and 3D nano-devices*
Felix Holzner, SwissLitho AG
- 12:30 Lunch
Food & drinks provided
- 13:30 *Nanometer precise grayscale lithography for nanofluidic sorting devices*
Armin Knoll, IBM Research Zurich
- 14:00 *Writing magnetism with thermal probes: multidimensional spin-textures and magnonics*
Edoardo Albisetti, Politecnico di Milano
- 14:30 *Micro/nanomanufacturing for fragile material systems*
Jürgen Brugger, EPFL Lausanne
- 15:15 Closing
Stay for further discussions with drinks & snacks

Sponsors & Exhibitors



4D-3D

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SWISSLITHO AG
Innovative Nanofabrication Tools



GenISys
Advancing the Standard